

ABSTRACT

5 Provided is a photomask blank including, on a substrate, a processing film and a
film made of a material containing chromium which is formed to be in contact with the
processing film and has a three-layer structure of first, second and third layers, each of
which contains chromium, oxygen, and nitrogen, wherein the first layer has a chromium
content of 40 atomic% or less, an oxygen content of 50 atomic% or more, a nitrogen content
10 of 10 atomic% or less, and a thickness of 20 nm or more, the second layer has a chromium
content of 50 atomic% or more, an oxygen content of 20 atomic% or less, and a nitrogen
content of 30 atomic% or more, and the third layer has a chromium content of 40 atomic%
or less, an oxygen content of 50 atomic% or more, and a nitrogen content of 10 atomic%
or less.

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[Fig.1]